**CNSE NanoFab Tool Calibration Form**

**DATE: \_\_6/20/2016\_\_\_\_\_\_\_\_\_\_\_\_\_\_\_\_**

**Tool Description: \_E-beam Evaporator #2\_\_\_\_\_\_\_**

**Test: Deposition thickness and uniformity**

**Run Parameters:**

**Sample size: 4” silicon wafer**

**Material: Titanium 100 ang., Palladium 200 ang.**

**Starting chamber pressure: 4.0 x 10-6 Torr**

**Rotation speed: 50%**

**Evaporation rate: 1 ang/sec.**

**Tooling factor: 84%**

**Calibration tool: Dimension 3100 AFM**

**Results:**

**Uniformity: 1.3% using three measurements (1 top, 1 center, 1 bottom)**

**Requested thickness: 300 angstrom**

**Measured thickness: 304 angstrom avg.**

**Engineer: CNSE Staff\_Frank Lee\_\_\_\_\_\_\_\_\_\_\_\_\_\_\_\_\_**

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